

EAST Search History

| Ref # | Hits | Search Query | DBs | Default Operator | Plurals | Time Stamp |
|-------|--------|--|---|------------------|---------|------------------|
| L1 | 4 | ("6206760" "6402598" "6405399" "6595831").PN. | US-PGPUB; USPAT | OR | ON | 2006/11/30 13:47 |
| S1 | 225 | sato-shuzo.in. yasuda-zenya.in. komai-naoki.in. | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/09/05 17:46 |
| S2 | 3534 | 205/640-686.ccls. | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/09/05 17:48 |
| S3 | 10 | S1 and S2 | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/09/06 10:55 |
| S4 | 307866 | sony.as. | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/09/05 17:54 |
| S5 | 11 | S4 and S2 | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/09/05 17:54 |
| S6 | 8 | S5 not S3 | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/09/05 17:56 |
| S7 | 308349 | centripetal centrifugal | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/09/05 17:57 |

EAST Search History

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| S8 | 79 | S7 and S2 | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/09/05 17:58 |
| S9 | 452 | (drop dropp\$3 place plac\$3 deliver deliver\$3 dispose disposed apply applying applicat\$3 discharg\$3 flow flow\$3) with (electrolyte slurry "electropolishing fluid") with (center middle inner) with (workpiece work substrate microelectronic wafer) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/09/06 11:05 |
| S10 | 452 | (drop dropp\$3 place plac\$3 deliver deliver\$3 dispose disposed apply applying applicat\$3 discharg\$3 (flow not (flow adj rate)) flow\$3) with (electrolyte slurry "electropolishing fluid") with (center middle inner) with (workpiece work substrate microelectronic wafer) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/09/06 11:01 |
| S11 | 149 | ((drop dropp\$3 place plac\$3 deliver deliver\$3 dispose disposed apply applying applicat\$3 discharg\$3 flow flow\$3) with (electrolyte slurry "electropolishing fluid") with (center middle inner) with (pad)) and (workpiece work substrate microelectronic wafer) and (CMP (chemical adj mechanical polishing) electropolishing electropolish) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/09/06 11:06 |
| S12 | 66 | ((drop dropp\$3 place plac\$3 deliver deliver\$3 dispose disposed apply applying applicat\$3 discharg\$3 flow flow\$3) with (electrolyte slurry "electropolishing fluid") with ((center middle inner) near2 (pad))) and (workpiece work substrate microelectronic wafer) and (CMP (chemical adj mechanical polishing) electropolishing electropolish) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/09/06 12:01 |

EAST Search History

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| S13 | 18 | (US-20040149592-\$ or US-20020088709-\$ or US-20030141201-\$ or US-20030121797-\$ or US-20050124267-\$ or US-20050113006-\$ or US-20040242126-\$ or US-20050037936-\$ or US-20040116313-\$ or US-20040087257-\$).did. or (US-6582578-\$ or US-6551488-\$ or US-6899609-\$ or US-6461230-\$ or US-6409577-\$ or US-6238270-\$ or US-5879226-\$ or US-5866480-\$). did. | US-PGPUB; USPAT | OR | ON | 2006/09/06 11:49 |
| S14 | 0 | S13 and ((recycle cup collect) with (electrolyte slurry "polishing fluid")) | US-PGPUB; USPAT | OR | ON | 2006/09/06 11:50 |
| S15 | 18 | (US-20040149592-\$ or US-20020088709-\$ or US-20030141201-\$ or US-20030121797-\$ or US-20050124267-\$ or US-20050113006-\$ or US-20040242126-\$ or US-20050037936-\$ or US-20040116313-\$ or US-20040087257-\$).did. or (US-6582578-\$ or US-6551488-\$ or US-6899609-\$ or US-6461230-\$ or US-6409577-\$ or US-6238270-\$ or US-5879226-\$ or US-5866480-\$). did. | US-PGPUB; USPAT | OR | ON | 2006/09/06 11:57 |
| S16 | 6 | S15 and (cathode anode electrode) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/09/06 11:57 |
| S17 | 4 | ((drop dropp\$3 place plac\$3 deliver deliver\$3 dispose disposed apply applying applicat\$3 discharg\$3 flow flow\$3) with (electrolyte slurry "electropolishing fluid") with ((center middle inner) near2 (pad))) and (workpiece work substrate microelectronic wafer) and (EMP (electomechanical adj polishing) electropolishing electropolish) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/09/06 12:05 |

EAST Search History

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| S18 | 3534 | 205/640-686.ccls. | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/09/06 12:05 |
| S19 | 522 | S18 and (ECMP (electrochemical adj mechanical adj polishing) electropolishing electropolish) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/09/06 12:06 |
| S20 | 138 | S18 and (ECMP (electrochemical adj mechanical adj polishing) electropolishing electropolish) and pad | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/09/06 12:08 |
| S21 | 8 | S18 and (ECMP (electrochemical adj mechanical adj polishing) electropolishing electropolish) and (pad near2 (center middle)) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/09/06 12:07 |
| S22 | 213 | (ECMP CMP (chemical adj mechanical adj (polish polish\$3 planariz\$3 etch etch\$3)) (electrochemical adj mechanical adj (polish polish\$3 planariz\$3 etch etch\$3))) and ((slurry solution electrolyte) same (((abrasive adj grains) alumina)) with (control specifying specif\$3 controll\$3)) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/11/29 16:57 |
| S23 | 0 | (ECMP (electrochemical adj mechanical adj (polish polish\$3 planariz\$3 etch etch\$3))) and ((slurry solution electrolyte) same (((abrasive adj grains) alumina)) with (control specifying specif\$3 controll\$3)) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/11/29 16:56 |
| S24 | 213 | (CMP (chemical adj mechanical adj (polish polish\$3 planariz\$3 etch etch\$3))) and ((slurry solution electrolyte) same (((abrasive adj grains) alumina)) with (control specifying specif\$3 controll\$3)) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/11/29 16:58 |

EAST Search History

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| S25 | 213 | (CMP (chemical adj mechanical adj (polish polish\$3 planariz\$3 etch etch\$3))) and ((slurry solution electrolyte) same (((abrasive adj grains) alumina) with (control specifying specif\$3 controll\$3))) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/11/29 17:00 |
| S26 | 159 | (CMP (chemical adj mechanical adj (polish polish\$3 planariz\$3 etch etch\$3))) and ((slurry solution electrolyte) same ((alumina) with (control specifying specif\$3 controll\$3))) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/11/29 16:59 |
| S27 | 23 | (US-20040149592-\$ or US-20030141201-\$ or US-20030121797-\$ or US-20020088709-\$ or US-20030116446-\$ or US-20050124267-\$ or US-20050113006-\$ or US-20050037936-\$ or US-20040242126-\$ or US-20040116313-\$ or US-20040087257-\$ or US-20050145507-\$).did. or (US-6551488-\$ or US-6582578-\$ or US-5866480-\$ or US-6899609-\$ or US-6461230-\$ or US-6409577-\$ or US-6238270-\$ or US-5879226-\$ or US-6464855-\$ or US-5911619-\$ or US-5807165-\$).did. | US-PGPUB; USPAT | OR | ON | 2006/11/29 17:00 |
| S28 | 1 | S27 and S25 | US-PGPUB; USPAT | OR | ON | 2006/11/29 17:00 |
| S29 | 144 | (CMP (chemical adj mechanical adj (polish polish\$3 planariz\$3 etch etch\$3))) and ((slurry solution electrolyte) with (((abrasive adj grains) alumina) with (control specifying specif\$3 controll\$3))) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/11/29 17:08 |
| S30 | 1 | (CMP (chemical adj mechanical adj (polish polish\$3 planariz\$3 etch etch\$3))) and (nozzle same (slurry solution electrolyte) with (((abrasive adj grains) alumina) with (control specifying specif\$3 controll\$3))) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/11/29 17:03 |
| S31 | 10 | (CMP (chemical adj mechanical adj (polish polish\$3 planariz\$3 etch etch\$3))) and ((slurry solution electrolyte) with (((abrasive adj grains) alumina) with (control specifying specif\$3 controll\$3))) and (nozzle with (slurry alumina (abrasive adj grain))) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/11/29 17:04 |

EAST Search History

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| S32 | 7 | (CMP (chemical adj mechanical adj (polish polish\$3 planariz\$3 etch etch\$3))) and ((slurry solution electrolyte) with (((abrasive adj grains) alumina) with (control specifying specif\$3 controll\$3) with amount)) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/11/29 17:21 |
| S33 | 7 | S32 not S31 | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/11/29 17:09 |
| S34 | 13 | ("2003/0116446").URPN. | USPAT | OR | ON | 2006/11/29 17:20 |

EAST Search History

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|--|-----|---|------------------------------|----|----|------------------|
| S35 | 146 | ("20010016469" "20010024878" "20010036746" "20010042690" "20020008036" "20020016064" "20020016073" "20020016272" "20020040100" "20020070126" "20020072309" "20020074230" "20020088709" "20020096659" "20020108861" "20020130049" "20020139055" "20020160698" "20030073385" "20030079416" "20030083214" "20030104762" "20030113996" "20030114004" "20030116445" "20030116446" "20030136055" "20030153184" "20030170091" "2582020" "3239441" "3873512" "4263113" "4663005" "4666683" "4793895" "4934102" "4992135" "5002645" "5096550" "5114548" "5129981" "5209816" "5217586" "5225034" "5256565" "5340370" "5391258" "5407526" "5534106" "5543032" "5567300" "5575706" "5770095" "5783489" "5800577" "5807165" "5846882" "5866031" "5880003" "5897375" "5911619" "5954997" "5965036" "6001730" "6004880" "6056864" "6063306" "6066030" "6068879" "6077412" "6083840" "6090239" "6096652" "6099604" "6103096" "6106728" "6117775" "6117783" "6117853" "6121152" "6126853" "6139763" "6143155" "6143656" "6153043" "6171352" "6176992" "6177026" "6190237" "6194317" "6206756" "6217416" "6218305" "6234870" "6238592" "6248222" "6258711" "6258721" "6273786" "6276996" "6280598" "6299741" "6303049" "6303551" "6310019" "6315803" "6315883" "6348076" "6354916" "6355075" "6355153" "6375693" "6379223" "6391166").PN. OR ("6395152" "6416685" "6419554" "6428721" "6429133" "6440186" "6440295" "6447371" "6454819" "6455479" "6508952" "6551935" "6555158" "6562719" "6565619" "6569349" "6579153" "6592742" "6593239" "6596638" "6602112" "6605537" "6616976" "6620215" "6653242" | US-PGPUB; USPAT; USOCR | OR | ON | 2006/11/29 17:21 |
| 11/30/2006 2:08:38 PM C:\Documents and Settings\jmsmith1\My Documents\EAST\Workspaces\10762691.wsp | | | | | | |

EAST Search History

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|-----|---|---------------------------------|---|----|----|------------------|
| S36 | 6 | S35 and (substrate adj support) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/11/29 18:01 |
| S37 | 2 | "5807165".pn. | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/11/29 18:01 |